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C11
wherein the positive resist composition is coated on the surface of the silicon wafer.

Please add the following new claims:

B3
--6. The article of claim 1, wherein in the positive resist composition the amount of components of the novolac resin having a molecular weight of 1,000 or less is 25% or less based on the total amount of the novolac resin excluding unreacted phenol compound, the amounts being represented by the pattern areas of gel permeation chromatography, wherein the pattern areas refer to values measured by an UV detector at 254 nm and the molecular weight refers to a value based on that of polystyrene as a standard.

7. The article of claim 1, wherein the positive resist composition which further comprises a low molecular weight alkali-soluble phenol compound in an amount within a range of 3 to 40% by weight based on the total amount of the novolac resin and the low molecular weight alkali-soluble phenol compound.

8. The article of claim 1, wherein in the positive resist composition the thioxanthone compound of the formula (I) is